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VOL. 2, NO. 6, 2013



ECS JOURNAL OF SOLID STATE
SCIENCE AND TECHNOLOGY



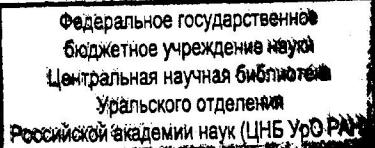


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